## **Basic Operations for MechGen Web Users**

Jia Jiang and William P. L. Carter

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MechGen is a computer program that can be used to generate gas-phase reactions of volatile organic compounds and the products they form at temperatures at or near 298 K and pressures at or near 1 atmosphere. The reactions can be generated in either in "single step" mode to see the predictions and documentation for a single reaction, or in "react completely" mode to also react the intermediates formed to obtain a complete mechanism leading to stable products. The stable products can then be reacted as separate operations. Results are displayed to the user or can be downloaded for further analysis.

MechGen can be accessed using the web interface that is currently available at: http://mechgen.cert.ucr.edu. This quick guide will walk through the basic operations for web users. If you are unable to access this website, please contact the author, William P. L. Carter: carter@cert.ucr.edu. Documents giving more information on MechGen and how it derives chemical mechanisms are available through the MechGen web site.

When first accessing the MechGen website, the user is presented with a login page shown on Figure 1. It includes form to give a username and a password for new users to create a user-specific "reactor" system, or for returning users to access that reactor. Once created, the username and password are necessary to login back to your own reactor system in the future.



## Main Menu

When first logged into the system, the user is presented with a web page with a reactor with the default settings when a new user reactor is created. In Figure 2, one reactant has been created and fully reacted for illustration. These sections of the web page in Figure 2 are as follows:

- <u>Header</u>. Identifies the user and reactor and gives links to reload, log out, or restore reactor defaults. Also indicates the current lumping method that controls how mechanisms are generated and processed.
- <u>Create VOC or radical reactant</u>. This section has a form to create a reactant. You can input SMILES directly, or use MechGen structure notation (similar to SMILES but displays all atoms). Click the links on the website for detailed explanations of "structure" and "assigned name".
- <u>Get information on reactants in contents</u>. This lists reactants that previously created by the user. It has links to go to the "Reactant Information" page for the reactant (discussed later). If a reactant has been fully reacted, there are links to access the reaction results. Note that radical reactants are not displayed in this list unless they have been completely reacted.
- <u>Reactor options</u>. This contains links to change options that control mechanism generation and lumping options. Restoring reactor defaults sets all these options to those for a new user.
- <u>Other information</u>. This section includes links to obtain general information about MechGen and SAPRC.
- <u>Advanced options</u>. Users can employ "user assignments" to add to or override the default mechanism assignments. This might be useful for advanced users for the purpose of developing new mechanisms consistent with new data or theories, or modeling experimental data that appear to be inconsistent with default MechGen predictions. This section is not covered in this quick startup guide; please read the complete user manual on MechGen website for further details.
- <u>User Account Section</u>. This section has links to log out, change user password, enable telnet logins, or completely delete this web and (if applicable) telnet account, or provide optional user information.

### SAPRC-22 MECHANISM GENERATION SYSTEM

Reactor for user1 [#6343] (Reload) (Log out) (Restore defaults)

Lumping method = Explicit mechanism with no lumping [#22447] (type=3) (Change)

### Create VOC or radical reactant

· Input the structure, SMILES string, or assigned name for a reactant

Create

· Create from the list of SAPRC VOC model species by compound type or from complete list (sorted by atom nos.)

### Get information on reactants in contents: (Delete all reactants)

 <u>MEK</u>: CH3-CH2-CO-CH3 [#21153] (reacted with OH, NO3, and HV) (<u>delete</u>) Reactions generated using Explicit mechanism with no lumping Explicit mechanism has 78 reactions and 63 species. Show (<u>reactions and products</u>). Send (<u>reactions</u>) or (<u>products</u>) Processed mechanism has 37 reactions and 47 species. Show (<u>reactions</u>). Send in (<u>tab-separated format</u>) or in (<u>SAPRC</u>. <u>RXN format</u>)

### Reactor options

- Temperature (°K)= 298 ; Presssure (atm)= 1.00 ; Atm PM (µg/m<sup>3</sup>)= 50 ; O<sub>2</sub> in air 20.95% ← Change
- H<sub>2</sub>O is absent (change)
- · Change lumping method, which is currently Explicit mechanism with no lumping
- View or change standard environments. Currently 4 are used for product yields and 3 are used to generate mechanisms.
- Light source code is "STD640Z0". (Info or Change)
- SIMPOL 1 vapor pressure estimates [#7402] (Change)
- <u>Restore reactor defaults</u>

### **Obtain information**

- <u>Show Estimation Methods</u>
- <u>Show assignments</u> in SAPRC-22 Mechanism Assignments (with 541 species)
- Show information related to the SAPRC-22 mechaniism
- Draft users manual (opens a PDF file in a separate window)

#### Advanced options

- Minimum 1-step yield for competing reactions: 0.50% ← Change
- Minimum estimated yields for peroxy intermediates to react during mechanism generation 0.50% (- Change
- User assignments are disabled (Enable or edit)
- The user mechanism option is not available when Explicit mechanism with no lumping is selcted.

#### Web user account actions

- Log out
- Change web login password (does not affect Telnet logins):
   Submit
- · Telnet login enabled. Click here to get information on telnet access and commands.
- · Completely delete the web and telnet accounts for user1 and associated data and log out.

#### Web user account actions

- Log out
- Change web login password (does not affect Telnet logins):
   Submit
- Telnet login enabled. <u>Click here</u> to get information on telnet access and commands.
- · Completely delete the web and telnet accounts for user1 and associated data and log out.
- Give or edit user information (optional). Clear field to delete. Submit

Name:	
Email:	
Other info:	

 Please email Bill Carter at <u>carter@cert.ucr.edu</u> if you have any comments or questions about this system or notice errors in its operation or in its chemical mechanism assignments or estimates.

Figure 2. Screen shot of most of the main menu for the web interface showing a previously created and reacted reactant but otherwise with the default settings.

## **Reactant Information Pages**

Reactant information pages are shown when new reactants are created, or existing reactions are selected from the main menu. The content of these pages varies depending on whether the reactant is a stable compound or an intermediate, and whether the reactant has undergone a "react completely" operation. Figure 3 and Figure 4 illustrate examples of a stable reactant methyl ethyl ketone and of one of the radicals formed after it reacts. The contents of these pages are as follows:

- <u>Header</u>. The top section gives basic information about the reactant, including its structure in both MechGen and SMILES format, and lumping information if applicable.
- <u>Generate Reactions.</u>

In the case of stable compounds, this section gives links to generate single step reactions or complete reactions of the various type that this reactant can undergo, which is reaction with OH, NO<sub>3</sub>, and photolysis in the case of MEK, but can also include unimolecular reactions or reactions with O<sub>3</sub>,  $O^{3}P$ , depending on the compound. If reactions of this compound have previously been used in deriving a SAPRC mechanism, the page also includes a "Get Reaction Assignments" link to obtain information about the assignments that were used in previous complete mechanism generations for this compound.

In the case of reactant pages for intermediates, this section gives the results of a single step reaction of this radical, and a link to react this radical completely.

- <u>Groups</u>. This section lists MechGen groups in the molecule and how they were used to estimate the heat of formation.
- <u>Estimated vapor pressure (stable reactants only)</u>. Information about how the vapor pressure is estimated.

## MEK: Methyl Ethyl Ketone CH<sub>3</sub>-CH<sub>2</sub>-CO-CH<sub>3</sub>

Smiles string: CCC(C)=O Molecular weight of C<sub>4</sub>H<sub>8</sub>O is 72.11

No assigned heat of formation. Estimated heat of formation is -57.13 kcal/mole. Estimated vapor pressure (SIMPOL.1) at 298.00 deg K is 1.61e-1 atm. Fraction in particle phase (with PM=50 ug/m3): 1.1e-7 VOC Type = Ketone

## **Generate Reactions**

React with OH: (Single step)		(Select to react completely $\Box$ )	
React with NO3:	(Single step)	(Select to react completely $\Box$ )	
React with HV:	(Single step)	(Select to react completely ])	

React completely with all, or React selected completely

### Get reaction assignments

### Groups сн<sub>3</sub>-сн<sub>2</sub>-со-сн<sub>3</sub>

# Group	Bonded To	Heat o	f Formation
1 -CH3	2	-10.04	C_(C)
2 -CH <sub>2</sub> -	1,3	-5.26	C_(C)(CO)
3 -CO-R	2,4	-31.79	CO_(C)(C)
4 -CH3	3	-10.04	C_(CO)

### Notes on heat of formation estimate:

- Hf(-CH3[1])= -10.04 C\_(C) (Holmes and Aubry (2011))
- Hf(-CH2-[2])= -5.26 C\_(C)(CO) (Holmes and Aubry (2011))
- Hf(-CO-R)= -31.79 CO\_(C)(C) (Holmes and Aubry (2011))
- Hf(-CH3[4])= -10.04 C\_(CO) (Holmes and Aubry (2011))

## Estimated vapor pressure at 298.00 deg K is 1.61e-1 atm.

Vapor pressures estimated using the SIMPOL1. method. Estimated for T = 298.00 deg K

Prm Description	N	Parm	Log(VP)
<pre>b0 zeroeth group (constant term)</pre>	1	1.842	1.84
b1 carbon number	4	-0.425	-1.70
b9 ketone	1	-0.936	-0.94
For CH3-CH2-CO-CH3 at T=298.0K: Estimated vapor pressure (atm) = 10^	-0.79	= 1.61e	-1

Figure 3. Screen shot of the reactant menu for a newly created reactant with default reactor settings, using MVK as an example.

	CH <sub>3</sub> -CO-CH <sub>2</sub> -CH <sub>2</sub> O. Radical type: A primary alkoxy radical center. Smiles string: CC(=O)CC[O] Molecular weight of C <sub>4</sub> H <sub>7</sub> O <sub>2</sub> is 87.10
Vapor	No assigned heat of formation. Estimated heat of formation is -40.96 kcal/mole. pressure cannot be estimated: Cannot estimate VP for radicals VOC Type = This is a -CH2O. radical.
	React completely
	Unimolecular or O2 reactions
CH3-CO-CH2-CH2O> <u>CH3-CO-CH2.</u> ·	+ <u>HCHO</u> (5.5%)
<ul> <li>Decomposition (T= 298K): k= 3.73.</li> <li>k= A*e^Ea/RT; A= 1.00e+14 s-1; F recommendations of Orlando et al (2</li> <li>Base Ea contribution for decomposi Base Ea contributions for decomposidecompositions of acyclic saturated</li> <li>Correction for -CO- substituent on t various types of acyclic, on-alkyl a</li> <li>Warning: This reaction is estimated 14.22 kcal/mole, so the estimated ac</li> </ul>	e+3 s-1. Ea= Base Ea contributions + corrections = 14.22 kcal/mol. A factor estimate based on 2003). tions forming a HCHO carbonyl product = 0.00 kcal/mol. Assigned to be zero (not independent). sitions forming -CH2(.) radicals = 15.51 kcal/mol. Adjusted to fit activation energies derived for hydrocarbon alkoxy radicals. he radical formed = -1.29 kcal/mol. Adjusted to fit activation energies for decompositions of lkoxy radicals. All the parameters for radicals formed from alkanes were optimized first. to be endothermic by 6.85 kcal/mole. However, this is less than the estimated activation energy of tivation energy is not modified.
CH3-CO-CH2-CH2O> <u>.CH2-CO-CH2-</u>	<u>CH2-OH</u> (0.3%)
<ul> <li>recommended by Vereecken and Pee</li> <li>Base Ea for abstractions from -CH isomerization rate constants for 1-bi</li> <li>Ring strain for 1,4 H-shift isomeriz</li> <li>Ea correction for substitution by -(energy due to this substituent derive OH from various organics.</li> <li>Ea correction when a -CO- is in th to be consistent with the rate constat (2010).</li> <li>Overall Ea including and all correction</li> </ul>	eters (2009) for structure-reactivity estimation purposes. [3[1] groups = 7.549 kcal/mol. Activation energies derived from fits of experimental 1,4-H-shift utoxy an 1-pentoxy radicals (Atkinson, 2007). zations = 0.000 kcal/mol. No ring strain correction is used for 1,4 H-shift isomerizations. CO- on the group with the abstracted hydrogen is 0.030 kcal/mole. Correction to the activation d from the correction factor for the effect of this substituent on rate constants for abstractions by e transition state ring next to a CH3 group with the shifted hydrogen is 4.314 kcal/mole. Adjusted and for CH3-CO-CH2-CH20> .CH2-CO-CH2-CH2-OH as calculated by Vereecken and Peeters ettions = 11.893 kcal.mole.
CH3-CO-CH2-CH2O. + O2 -> CH3-CO-(	CH2-CHO + HO2. (94.2%)
<ul> <li>O2 reaction (T= 298K, 20.9% O2):</li> <li>k= 2.38e-14 * exp(-0.38/RT) = 1.25</li> <li>Kinetic parameters are estimated to 300K rate constant was derived by a the Arrhenius parameters estimated</li> </ul>	k*[O2]= 6.43e+4 s-1 e-14 cm3 molec-1 s-1; T= 298 K. be approximately the same for reactions of O2 with all alkoxy radicals with -CH2O. groups. The averaging the recommended values from measurements for n-propoxy and n-butoxy radicals, with by assuming that the A factor is the same as that given for 1-propoxy.
	Groups сн <sub>3</sub> -со-сн <sub>2</sub> -сн <sub>2</sub> о.
Notes on heat of formation estima • Hf(-CH3[1])= -10.04 C_(CO) (Holt Hf(-CH3[1])= -10.04 C_(CO) (Holt	# Group       Bonded To       Heat of Formation         1       -CH3       2       -10.04       C_(CO)         2       -CO-R       1,3       -31.79       CO_(C)(C)         3       -CH2-       2,4       -5.26       C_(C)(CO)         4       -CH2O.       3       -7.89       C_(C)(O*)         14.02       O*_(C)       O*_(C)       O*_(C)

Figure 4. Screen shot of the reactant page for a newly created radical reactant with default reactor settings, using one of the radicals formed in the initial reactions of OH with MEK as the example.

## **Generating Single Step Reactions**

Generating single step reactions is the best means to obtain information about reactions of individual compounds or radicals, and obtaining documentation information about how the results are derived or assigned. Once a single step reaction is generated, an associated single step reaction results page will be displayed.

These consist of lists of reactions and estimation methods, or mechanism assignments used. Example of single step reaction output for a stable reactant is shown in Figure 5.

## MVK: Methylvinyl ketone CH<sub>2</sub>=CH-CO-CH<sub>3</sub>

Smiles string: C=CC(C)=O Molecular weight of  $C_4H_6O$  is 70.09

No assigned heat of formation. Estimated heat of formation is -28.16 kcal/mole. Estimated vapor pressure at 298K is 1.26e-1 atm. Fraction in particle phase (with PM=50 ug/m3): 1.4e-7. VOC Type – Alpha unsaturated ketones

## **Reactions with OH**

CH2-CH-CO-CH3 + OH -> <u>CH3-CO-CH[.]-CH2-OH</u> (70.0%)

- Assigned total rate constant = 2.01e-11 = 2.60e-12 \* exp(1.212/RT) (T=298) cm3 molec-1 s-1. From the Compilation of McGillen et al (2020), as updated to version 2.1.0, June 23, 2021. https://doi.org/10.25326/mh4q-y215
- Rate constant for this reaction = 1.41e-11 cm3 molec-1 s-1 (70.0%). Based on product distribution of Tuazon and Atkinson (1989), as discussed by Carter and Atkinson (1996)

CH2=CH-CO-CH3 + OH -> <u>CH3-CO-CH(CH2.)-OH</u> (30.0%)

• Rate constant for this reaction (see above for total) = 6.04e-12 cm3 molec-1 s-1 (30.0%). Based on product distribution of Tuazon and Atkinson (1989), as discussed by Carter and Atkinson (1996)

• Assigned Total kOH for T=298 and 1.00 atm. = 2.01e-11 cm3 molec-1 s-1.

From the Compilation of McGillen et al (2020), as updated to version 2.1.0, June 23, 2021. https://doi.org/10.25326/mh4q-y215

# Figure 5. Screen shot of the portion of the single step reaction results page from reacting MVK with OH radicals.

## **Full Mechanism Generation**

The full mechanism generation process involves reacting all radicals formed in the initial reactions, then reacting the intermediates formed that need to be reacted, until only stable or species or basic species that do not need to be reacted remain. This can take a significant amount of time for larger molecules.

If the compound has more than 9 groups, the "Generate Reaction" section will not contain any active links to generate full reactions -- only single step reactions can be generated using the web system for such compounds. Telnet logins are required to generate mechanisms for login compounds. The main menu (Figure 1) has links to create a telnet login.

Once the full reaction generation is completed, a page showing the generated reaction is displayed with links for downloading the reaction or product lists. An example of the portions of such a page is shown as Figure 6.

In Figure 6, the top part of the page has links for downloading the list of products and reactants in the explicit, minimally processed, and (if applicable) lumped mechanisms in various formats. The download options include the following:

**Full mechanism (reactions)**: Reactions, rate constant parameters, and branching ratios in tabseparated format. Columns in this spreadsheet include reaction number, A, Ea, and B parameters for calculating temperature dependences where  $k(T)=A^*exp(-Ea/T)^*(T/300)^B$ , the weighting factor used during mechanism generation, the rate constant at the default temperature, and the reaction itself. For photolysis reactions, the name of the SAPRC-22 photolysis file is given in the column used for Ea and the overall quantum yield is in the column used for B, and the rate constant is shown for overhead sunlight for standard reaction conditions.

<u>Full mechanism (Products)</u>: List of products and their estimated yields for the standard environmental conditions.

**Processed mechanism (reactions & tab-separated format)**: List of products and intermediates (steady state species) in the minimally reduced processed mechanism. The product and intermediate listings include columns with the product or intermediate number, the name used for the product or intermediate in the reaction listings (either a standard SAPRC name or system generated), and the structure. The reaction section includes columns with the reaction number, A, Ea, and B parameters and rate constant at the default temperature (or photolysis file names and quantum yields and photolysis rates for overhead sunlight for photolysis reactions), and the reactions.

**Processed mechanism in (SAPRC .RXN format)**: This gives the processed mechanism in the format that can be used with SAPRC base mechanism and the SAPRC box modeling software. Links to obtain the SAPRC mechanism files and software are available at https://intra.engr.ucr.edu/~carter/SAPRC/SAPRC/files.htm.

Mechanism generated using Explicit mechanism with no lumping Full mechanism has 39 reactions and 35 species. Download tab-separated files with (reactions) or (products) Processed mechanism has 16 reactions and 20 species. Show (reactions). Send in (tab-separated format) or in (SAPRC .RXN format) Full set of reactions with OH Full set of reactions with OH Rxn k Fac Weight Reaction 3.15e-13 28% 28.4% CH3-CH2-CH3 + OH -> CH3-CH2-CH2. + H20 1 71.6% CH3-CH2-CH3 + OH -> CH3-CH[.]-CH3 + H20 7.94e-13 72% 2 71.6% CH3-CH[.]-CH3 + 02 -> CH3-CH[00.]-CH3 З 100% 8.75e-12 68.7% CH3-CH[00.]-CH3 + NO -> CH3-CH[0.]-CH3 + NO2 4 96% 3.70e-13 CH3-CH[00.]-CH3 + NO -> CH3-CH(CH3)-ONO2 5 4% 2.9% 2.30e-12 100% 71.6% CH3-CH[00.]-CH3 + NO3 -> CH3-CH[0.]-CH3 + NO2 + O2 6 100% 7 9.92e-12 71.6% CH3-CH[00.]-CH3 + H02 -> CH3-CH(CH3)-0-OH + 02 8 7.80e-15 50% 35.8% CH3-CH[00.]-CH3 + R02 -> CH3-CH[0.]-CH3 + 02 + R0. 9 3.90e-15 25% 17.9% CH3-CH[00.]-CH3 + R02 -> CH3-CH(CH3)-OH + 02 + R0-alpha-H CH3-CH[00.]-CH3 + R02 -> CH3-CO-CH3 + 02 + ROH 10 3.90e-15 25% 17.9% 11 1.28e-11 80% 57.3% CH3-CH[00.]-CH3 + RCO3 -> CH3-CH[0.]-CH3 + 02 + RCO2. 3.20e-12 20% 14.3% CH3-CH[00.]-CH3 + RCO3 -> CH3-CO-CH3 + O2 + RCO-OH 12 13 3.63e+2 1% 2.4% CH3-CH[0.]-CH3 -> CH3-CH0 + CH3. 14 3.56e+4 99% 230.9% СНЗ-СН[0.]-СНЗ + 02 -> СНЗ-СО-СНЗ + НО2. 15 100% CH3-CH2-CH2. + 02 -> CH3-CH2-CH200. 28.4% 8.75e-12 27.3% CH3-CH2-CH200. + NO -> CH3-CH2-CH20. + NO2 16 96% 1.2% 3.70e-13 4% CH3-CH2-CH200. + NO -> CH3-CH2-CH2-ONO2 17 18 2.30e-12 100% 28.4% CH3-CH2-CH200. + NO3 -> CH3-CH2-CH20. + NO2 + O2 (not all reactions shown) 2.1% CH300. + RC03 -> CH30. + 02 + RC02. 37 1.22e-11 90% 38 1.35e-12 10% 0.2% CH300. + RC03 -> HCH0 + 02 + RC0-0H 100% 7.5% CH30. + 02 -> HCH0 + H02. 39 8.21e+3 SAPRC-22 photolysis rates (sec-1) for Z=0, calculated using actinic fluxes used by the Carter (1994) reactivity sce Mechanism Generation options: T=298; P=1.0; O2=0.2095; MinYld=0.0050; Lumptype=3; Environ: HighNOxenv, LowNOxEnv, NightEnv Products from reacting under standard conditions Explicit products formed when PROPANE reacts with OH under the following conditions: Condition Description Mid NOx Mid NOx standard urban conditions (near EBIR) High NOx High NOx urban conditions (near MIR) Low NOx downwind conditions (NOx = MOIR NOx/10) Low NOx Nighttime conditions for multi-day, mid-NOx scenario Night Products listed in descending order of maximum yield Mid NOx High NOx Low NOx Night Explicit product or reacted 92.07% 96.63% 79.10% 64.14% NO2 88.10% 95.94% 65.00% 64.51% HO2. 65.33% 67.98% 57.50% 59.78% CH3-CO-CH3 26.07% 27.13% 22,94% 23.84% CH3-CH2-CH0 2.38% 2.77% 2.91% CH3-CH(CH3)-ONO2 2.80% 11.10% 11.12% CH3-CH(CH3)-0-OH 1.15% 1.10% 0.95% CH3-CH2-CH2-ONO2 0.60% 0.78% 0.84% 0.63% HCHO 0.66% 0.69% 0.57% 0.58% CH3-CH0 1.11% 4.40% 4.41% CH3-CH2-CH2-O-OH 0.13% 0.14% 0.12% 0.09% LostRads 0.05% 0.07% CH3-0-0H 0.01% \_ 0.00% Total < 0.05%

Figure 6. Portions of the web page displaying following a full reaction of propane with OH showing the explicit mechanism generated with the default (explicit) lumping approach

## **Modifying Mechanism Generation Options**

The options that affect mechanism generation and results processing in the reactor that the user can modify are listed and summarized in Table 1, which also gives the defaults for these options. These can be modified using links or input boxes in the "Reactor options" or "Advanced Options" sections of the main menu.

Option	Default	Description
Temperature	298 K	Default temperature in K
Pressure	1.0 atm	Default pressure in atmospheres
O2 in air	20.95%	Mole fraction of $O_2$ in the reaction environment
Atm PM	$50 \mu\text{g/m}^3$	Atmospheric particle levels used to estimate fractions of reactants in the particle phase if their vapor pressures can be estimated
H2O	Present	Used to determine of some intermediates react with water
Lumping method	Explicit	Lumping method used when generating full reactions and processing results. Currently available options are "Explicit" or SAPRC-11 or versions of SAPRC-22.
Standard Environments	3 Daytime and 1 nighttime (urban)	Determines which environmental conditions are used for deriving estimated product yields and allows the user to control whether they are used determine which reactions can be treated as negligible.
Vapor pressure estimator	SIMPOL.1	Method used to estimate the vapor pressure that is displayed on the reactant information page for stable compounds. Available options are SIMPOL.1 <sup>a</sup> or EVAPORATION <sup>b</sup> .
		Advanced options
Minimum 1-step yield	0.5%	The minimum yield for a competing process in a single step reaction for it to be considered non-negligible during full mechanism generations
Minimum yield to react	0.5%	The minimum estimated yield for a peroxy radical intermediate to be reacted during full mechanism generation.
Mechanism	No user	This option is selected if the user wants to use user assignments that
Assignments	assignments	the user can create to add to or replace the standard used by MechGen.
User mechanisms	No user mechanisms	Users who select the SAPRC-22 lumping method can optionally add versions of the mechanism with selected reactant and product compounds being represented explicitly.

[a] Pankow, J. F. and W. E. Asher, Atmos. Chem. Phys., 8, 2773-2796, 2008. <u>https://doi.org/10.5194/acp-8-2773-2008</u>. [b] Compernolle, S., K. Ceulemans, and J.-F. Muller (2011), Atmos. Chem. Phys., 11, 9431-9450. <u>https://doi.org/10.5194/acp-11-9431-2011</u>.